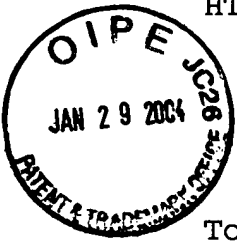


HTIRC-03-005



January 22, 2004

To: Commissioner for Patents
P.O.Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/714,305 11/14/03 |
Jei-Wei Chang et al.
SINGLE LAYER RESIST LIFTOFF PROCESS
FOR NANO TRACK WIDTH
| _____ |

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on January 27, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

 1/27/04

HTIRC-03-005

U.S. Patent 6,519,124 to Redon et al., "Magnetic Tunnel Junction Read Head Using a Hybrid, Low-Magnetization Flux Guide," discloses a conventional lift-off resist process.

U.S. Patent 5,212,044 to Liang et al., "Photoresist Composition Including Polyphenol and Sensitizer," describes a method of hardening a resist using an ion beam.

Sincerely,

A handwritten signature in black ink, appearing to be 'SBA', written over the printed name.

Stephen B. Ackerman,
Reg. No. 37761

Application Number

10/714.305

Jei-Wei Chang et al.

11/14/03

Group Affinity

U. S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Portion or Pages, Etc.)

[illegible]

DATE COMPLETED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.